

CMP Pad Conditioners

Our CMP Pad Conditioners have been tested and proven in production by major semiconductor manufactures in USA, Europe, Taiwan and Korea. We have the capability to meet the needs of each customer by providing customized disks.

Our CMP disks are available in various production quantities, shapes and sizes for all CMP production platforms.

- Applied Materials Mirra and Mirra - Mesa
- EBARA EPO-113, 222, 333
- Strasbaugh DS-SP, 6ED
- Speedfam / IPEC

CMP Processes:

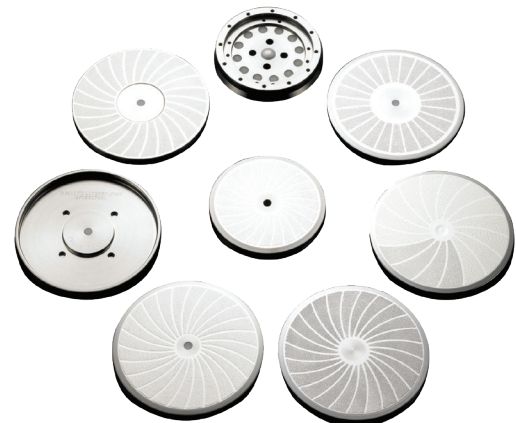
- Oxide CMP : BPSG, TEOS, SC
- Metal CMP : W, CU
- STI, PGI etc.

Features:

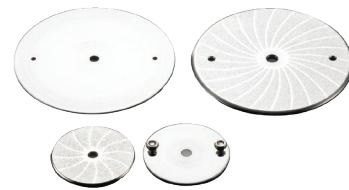
- Excellent Diamond Retention
- Longer Disk Life
- Increased Pad Life
- Significant Lowering of Micro Scratch

Saesol CMP pad conditioners are recommended by Dow Chemicals

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AMAT Machine



Strasbaugh/Lam/Doosan Machine



EBARA Machine

